IN THE CLAIMS

This listing of claims replaces all prior versions and listings of the claims in the abovereferenced application.

1. (Original) A semiconductor light emitting device comprising a light emitting layer disposed between an n-type region and a p-type region, wherein:

the light emitting layer is wurtzite;

- a <0001> axis is substantially parallel to a top surface of the light emitting layer; and the light emitting layer has a thickness greater than 25 Å.
- 2. (Original) The device of claim 1 wherein the light emitting layer has a thickness greater than 50 Å.
- 3. (Original) The device of claim 1 wherein the light emitting layer has a thickness greater than 90 Å.
- 4. (Original) The device of claim 1 wherein the light emitting layer has a thickness greater than 150 Å.
- 5. (Original) The structure of claim 1 wherein the light emitting layer comprises {1120} InGaN.
- 6. (Original) The structure of claim 1 wherein the light emitting layer comprises {1010} InGaN.
- (Original) The structure of claim 1 wherein the light emitting layer comprises
 one of AlGaN and AlinGaN.
- 8. (Original) The device of claim 1 wherein a composition of indium in the light emitting layer is graded from a first indium composition in a first portion of the light emitting layer proximate the n-type region to a second indium composition in a second portion of the light emitting layer proximate the p-type region.
- 9. (Original) The device of claim 8 wherein the first composition is greater than the second composition.
- 10. (Original) The device of claim 8 wherein the first composition is less than the second composition.
- 11. (Original) The device of claim 8 wherein a composition of aluminum in the light emitting layer is graded from a first aluminum composition in a first portion of the light emitting layer proximate the n-type region to a second aluminum composition in a second portion of the light emitting layer proximate the p-type region.

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- 12. (Original) The device of claim 1 wherein a composition of aluminum in the light emitting layer is graded from a first aluminum composition in a first portion of the light emitting layer proximate the n-type region to a second aluminum composition in a second portion of the light emitting layer proximate the p-type region.
- 13. (Original) The device of claim 12 wherein the first composition is greater than the second composition.
- 14. (Original) The device of claim 12 wherein the first composition is less than the second composition.
- 15. (Original) The device of claim 1 wherein the light emitting layer is a first quantum well, the device further comprising:
 - a second quantum well; and
 - a barrier layer disposed between the first and second quantum well;
- wherein the first quantum well, second quantum well, and barrier layer form an active region.
- 16. (Original) The device of claim 15 wherein an indium composition in one of the first and second quantum wells is graded.
- 17. (Original) The device of claim 15 wherein the barrier layer has a graded composition.
- 18. (Currently Amended) The device of claim 15 <u>further comprising first and</u> second cladding layers, wherein the active region is disposed between <u>the</u> first and second cladding layers.
- 19. (Currently Amended) The device of claim 45 18 wherein the first and second cladding layers have a larger band gap than the first and second quantum wells.
 - 20. (Currently Amended) The device of claim 15 18 wherein:

each of the first and second cladding layers is graded from a first band gap in a portion of the cladding layers adjacent to the active region to a second band gap in a portion of the cladding layers spaced apart from the active region; and

the second band gap is greater than the first band gap.

- 21. (Original) The device of claim 20 wherein a composition of indium in the first and second cladding layers is graded.
- 22. (Original) The device of claim 1 wherein the device operates at a current density greater than 10 A/cm².

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(Original) The device of claim 1 wherein the device operates at a current 23. density greater than 100 A/cm².

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